

Fig. 1(a) Prior Art

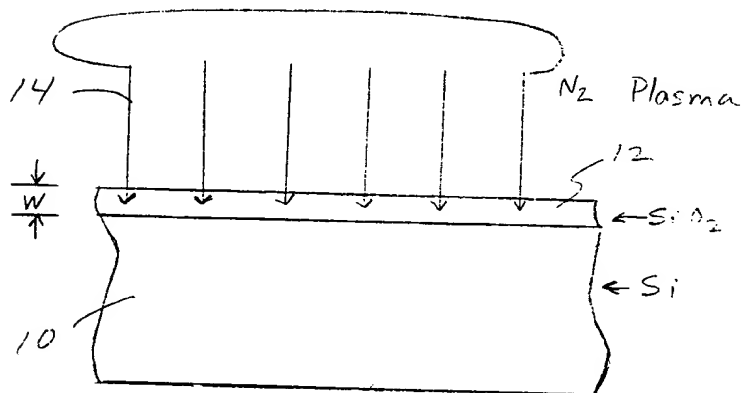


Fig. 1(b) Prior Art

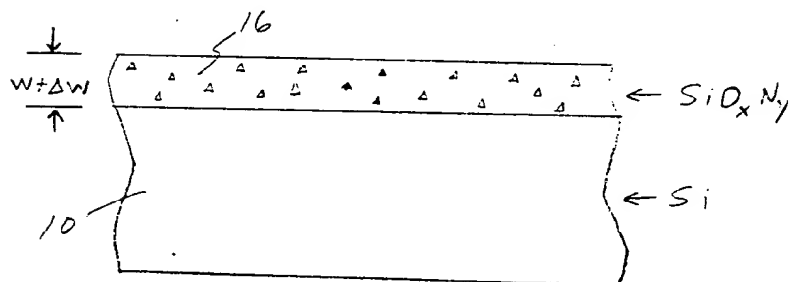


Fig. 1(c) Prior Art

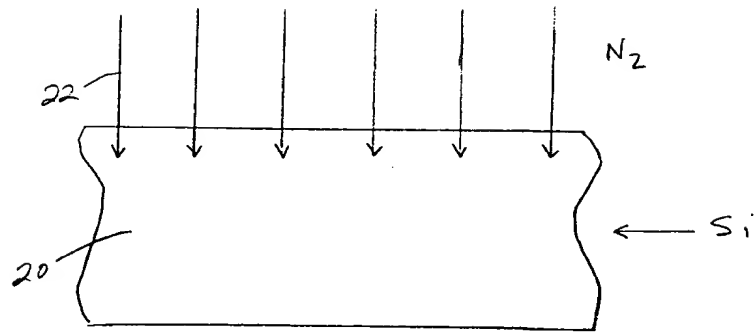


Fig. 2(a)

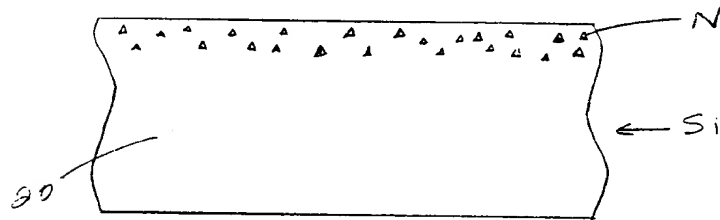


Fig. 2(b)

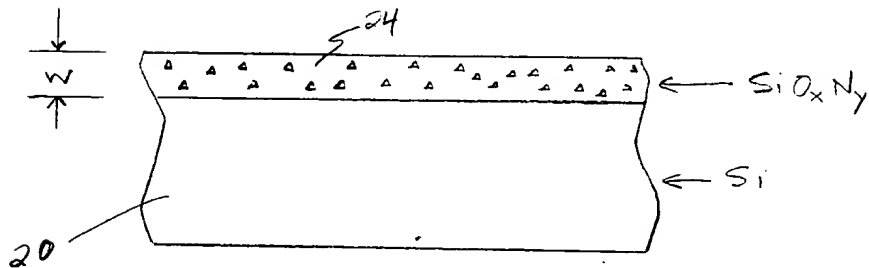


Fig. 2(c)

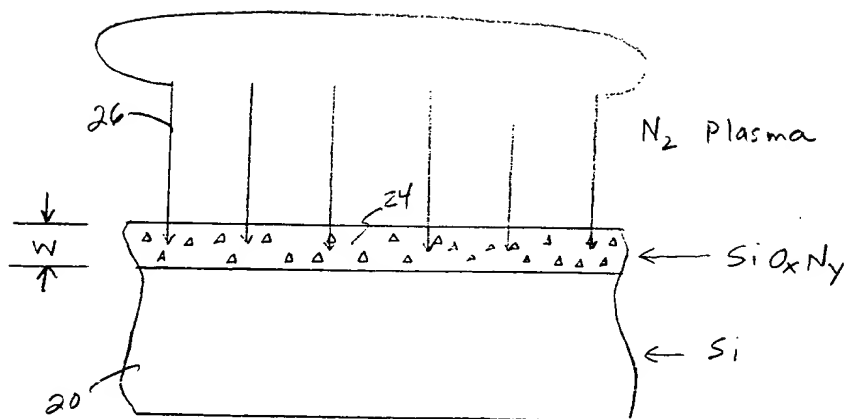


Fig. 2 (d)

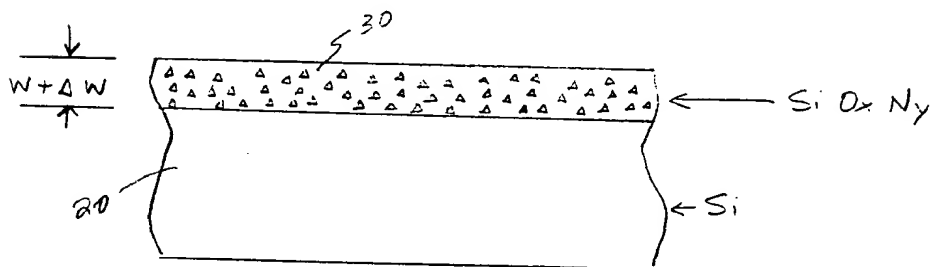


Fig. 2 (e)

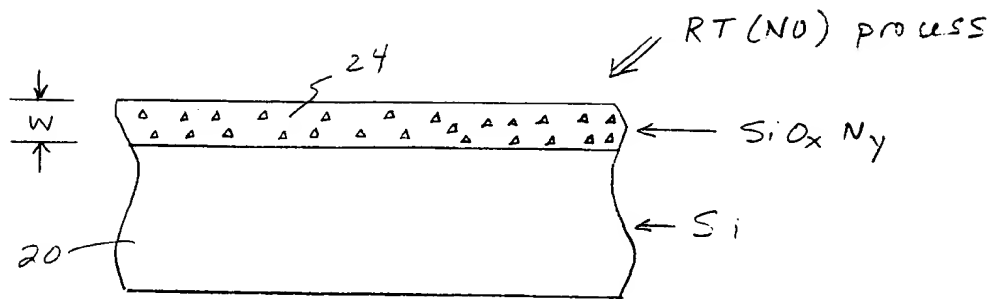


Fig. 3(a)

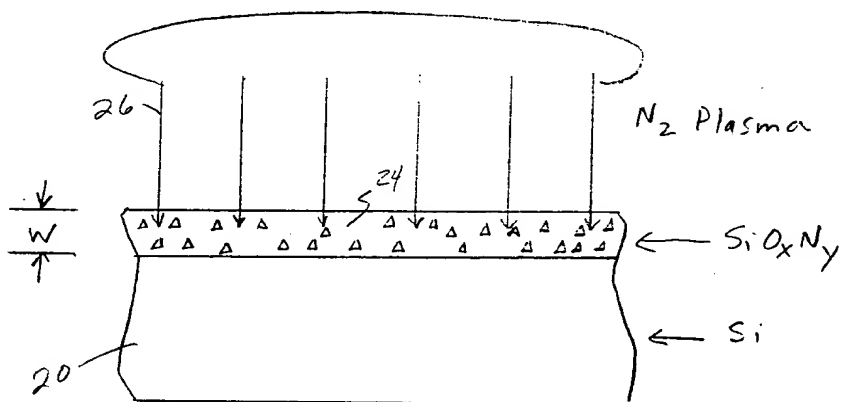


Fig. 3(b)

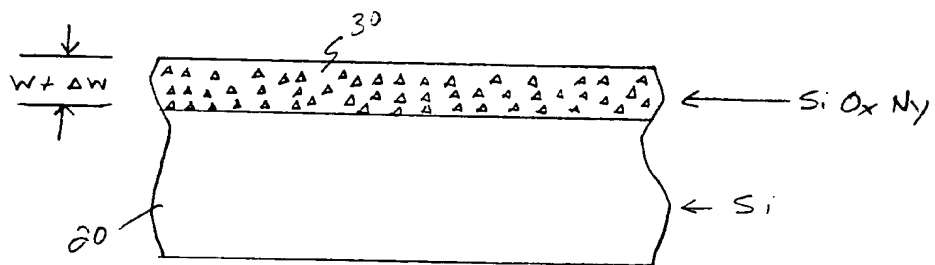
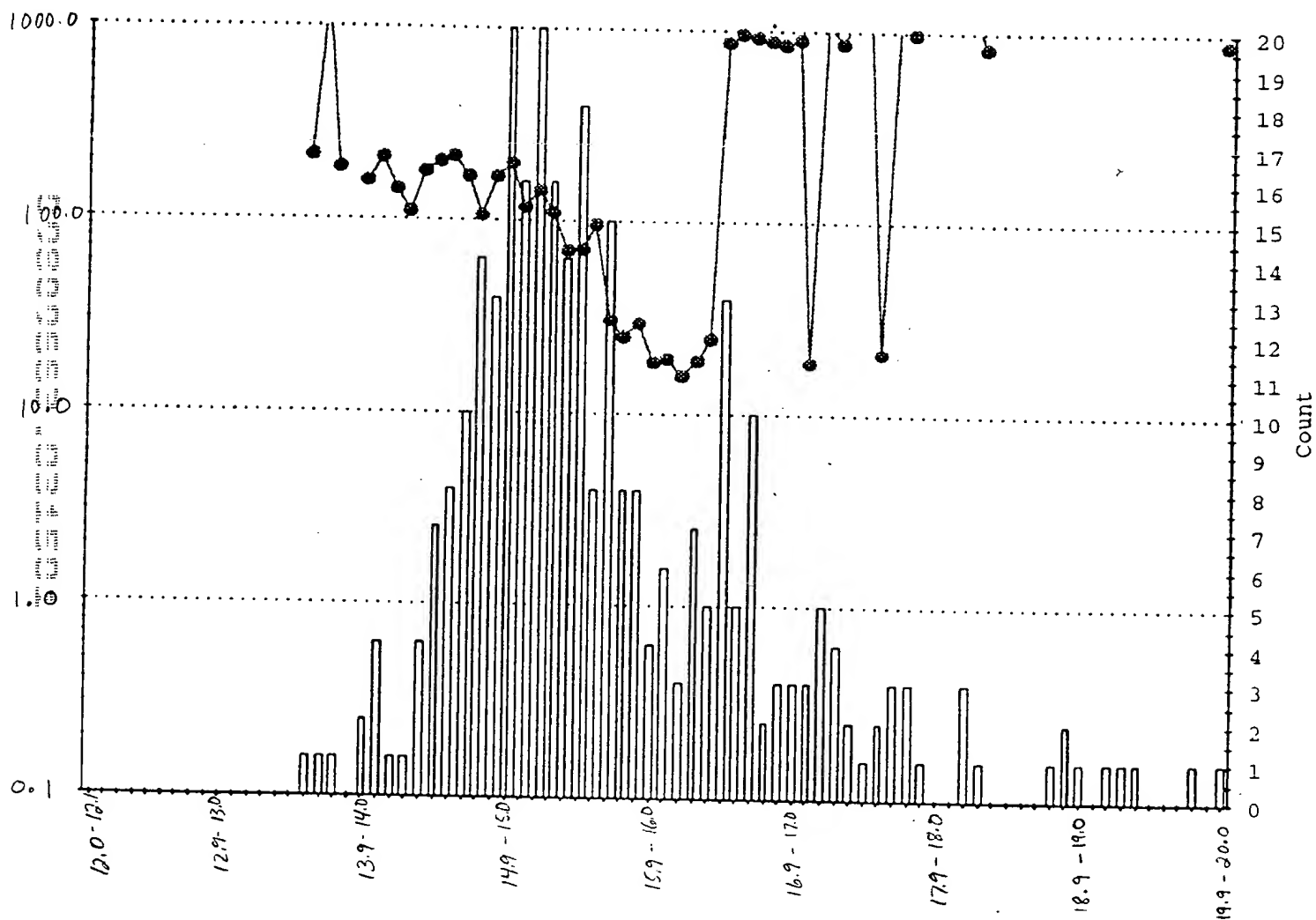


Fig. 3(c)

SiO₂ only



Gate Thickness (Å)

Fig. 4

SiO₂ + RPN
(Prior Art)

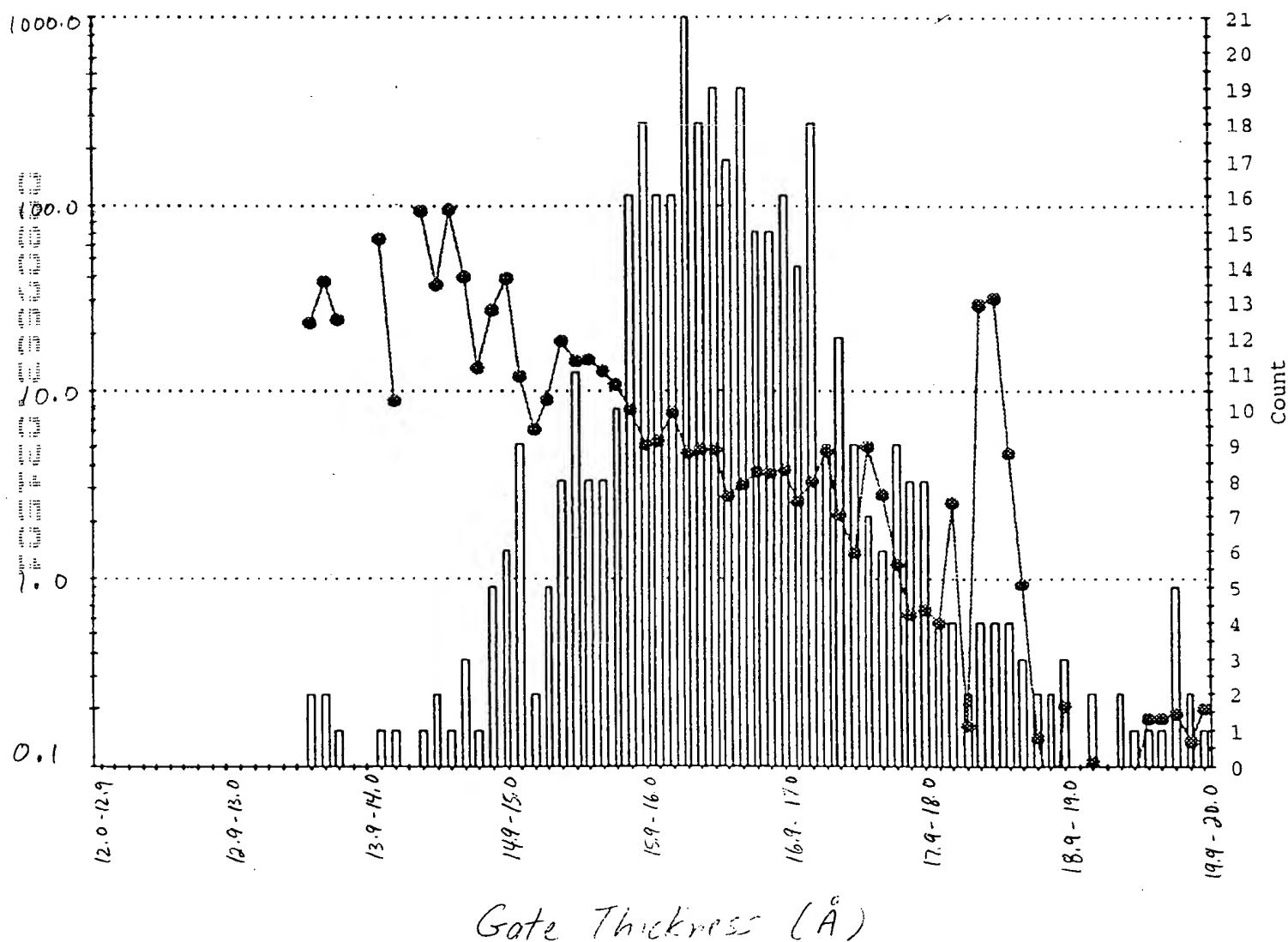


Fig. 5

$\text{SiO}_x\text{N}_y + \text{RPN}$

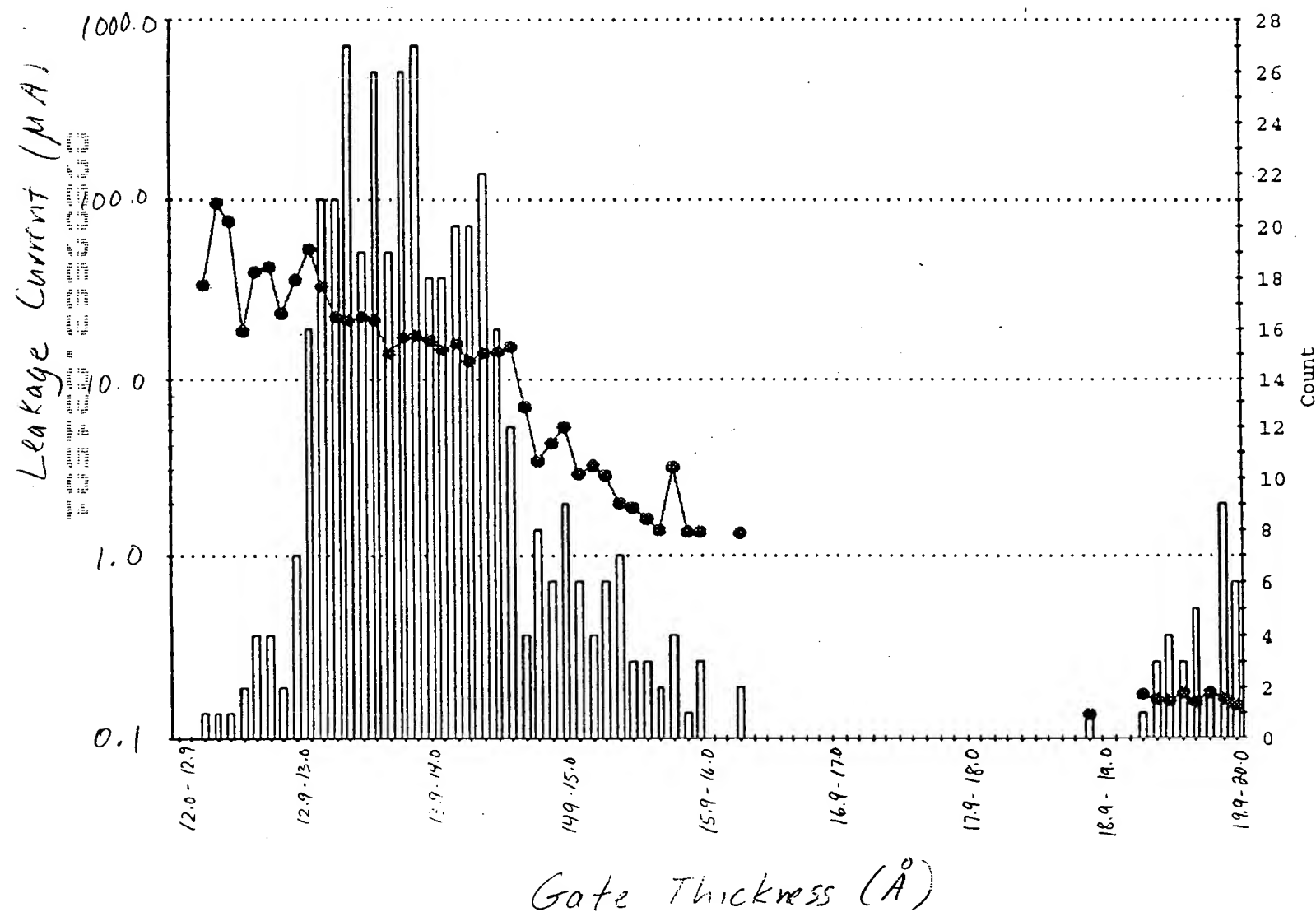


Fig. 6

Uniformity of Gate Film

	<u>Mean Thickness (nm)</u>	<u>σ</u>
RPN of SiO_2 (Dry)	1.74	0.287
RPN of SiO_2 (Wet)	1.68	0.115
RTNO	1.70	0.0293
RTNO + RPN @ 550°C	1.74	0.0246
RTNO + RPN @ 750°C	1.73	0.0296

Fig. 7

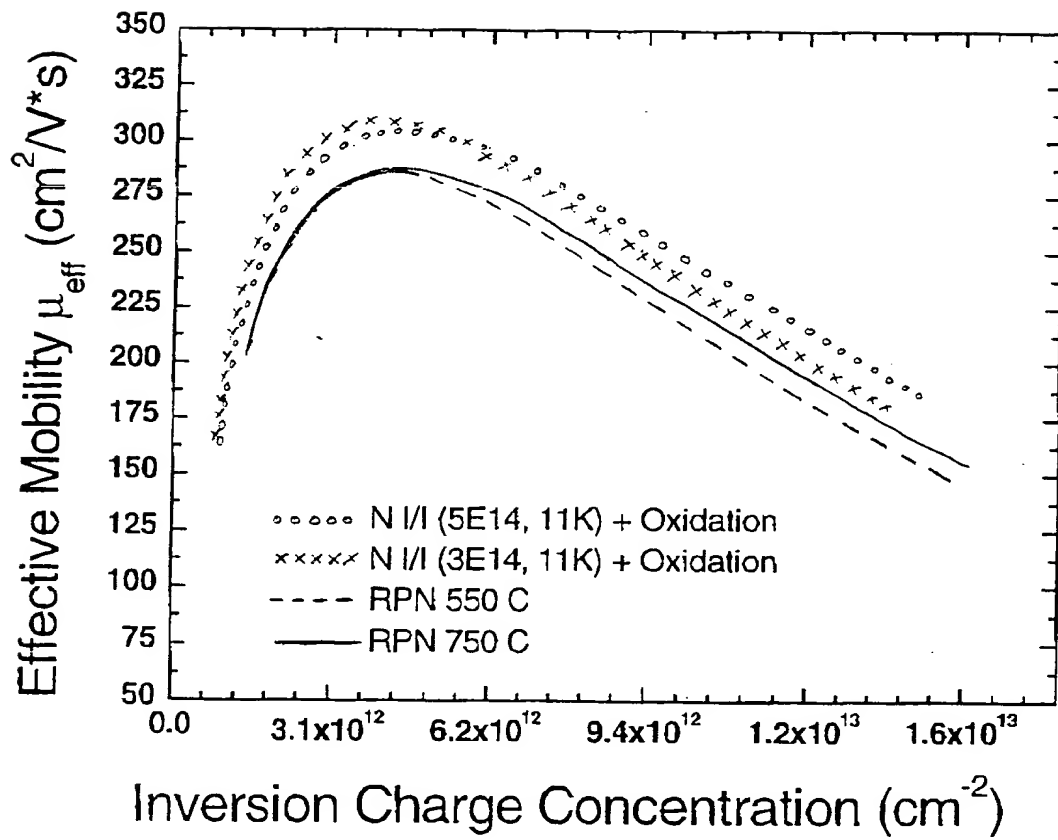


Figure 8